

FIG.1A(Prior Art)

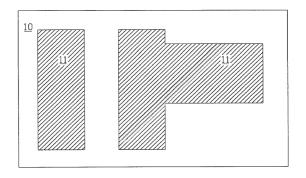


FIG.1B(Prior Art)

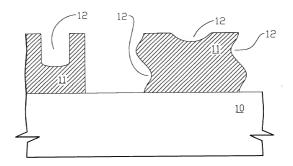


FIG.1C(Prior Art)

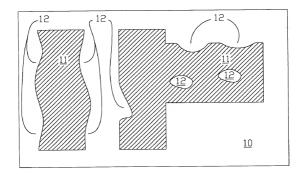


FIG.1D(Prior Art)

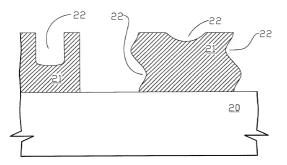


FIG.2A

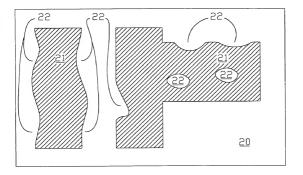


FIG.2B

## TITLE: METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST Inventor: Yen-Ting LU Docket No. 4425-168

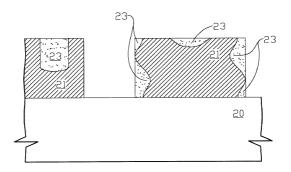


FIG.2C

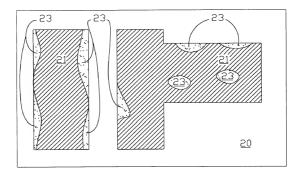


FIG.2D

## TITLE: METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST Inventor: Yen-Ting LU Docket No. 4425-168

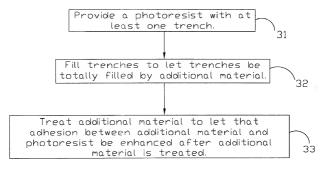


FIG.3A

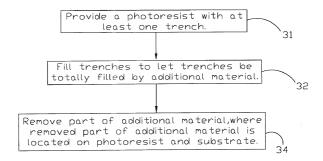


FIG.3B

## TITLE: METHOD FOR REDUCING LINE EDGE ROUGHNESS OF PHOTORESIST Inventor: Yen-Ting LU Docket No. 4425-168

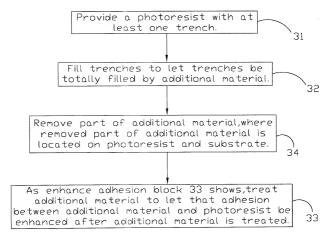


FIG.3C